## **Electronic Supplementary Information**

# One-Step Fabrication of Transparent and Conductive TiO<sub>x</sub>/Ag Nanowire Hybrid Thin Film with High Robustness<sup>†</sup>

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## **Experimental Details**

## I. Chemicals

Ag NW/ethanol dispersion (10 mg/mL,  $\sim$ 50.3 nm×15.7 µm) was bought from Blue Nano Inc. Titanium isopropoxide (98%), ethanolamine (AR) and 2-methoxyethanol (AR) were purchased from Aladdin Inc.

## II. Preparation of TiO<sub>x</sub>/Ag NW dispersion

TiO<sub>x</sub> sol-gel solution was firstly prepared according to a modified procedure.<sup>1</sup> 2.0 mL of titanium isopropoxide and 1.0 mL of ethanolamine were added into 10.0 mL of 2-methoxyethanol under magnetic stirring. Then, the mixed solution was putted on a hotplate at 100 °C for 2 h. Finally, an orange-red TiO<sub>x</sub> sol-gel solution was obtained. 1.0 mL of TiO<sub>x</sub> sol-gel solution (~40 mg TiO<sub>x</sub>) and 1.0 mL of Ag NW/ethanol

dispersion (~10 mg AgNWs) were mixed under magnetic stirring, forming TiO<sub>x</sub>/Ag NW dispersion.

#### Deposition of TiO<sub>x</sub>/Ag NW hybrid thin film

TiO<sub>x</sub>/Ag NW hybrid thin film was fabricated by a spin-casting process at 2500 rpm for 15 s, followed by a sintering process on a pre-heated hotplate at 180-280  $^{\circ}$ C for 2 min. A multi-step spin-casting method was utilized to achieve TiO<sub>x</sub>/Ag NW hybrid thin films with different AgNW densities.

#### **III.**Characterizations

The scanning electron microscope (SEM) images were taken using a Hitachi S-4800. UV-vis transmittance spectra were measured by Metash UV-5200. The sheet resistance was measured using a 4-point probe method with a Keithley 2400 source meter (Sheet resistance=measured resistance×4.532). The film thickness and surface roughness were measured by a step profilermeter (AMBIOS, XP-100).



Figure S1 XRD pattern of TiO<sub>x</sub>/Ag NW hybrid network



Figure S2. The stability of sheet resistance of transparent and conductive  $TiO_x/Ag$ 

NW hybrid thin film.



Figure S3 The transmittance spectra and sheet resistance of  $TiO_x/Ag$  NW hybrid thin films with different Ag/TiO<sub>x</sub> volume ratios.

# Reference

1. J. Y. Kim, K. Lee, N. E. Coates, D. Moses, T. Q. Nguyen, M. Dante and A.

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